Kavli Nanolab Delft
Enabling nanodevice fabrication

Recipe for AZ10XT resist

Application

Substrate preparation: it is preferable to process the silicon substrate by evaporation of HMDS at 150˚C for 45 sec, using the Delta RC80. Before use, take the resist out of the fridge and leave it for 30 minutes to get to room temperature.

Tone	Positive
Reference	Microchemicals
Spin coat	8.3 µm @2500 RPM
Pre bake	3 min @110˚C on hotplate
Rehydrate	30 min
Exposure time	Approx. ~24 sec @ 8.42 mW/cm^2
Development	6 min in AZ400K (1:4)
Stopping of development	30 sec in H_2O

Results

Spin curve